

Photomask Japan 2023

Best Paper Award Winners



Best Oral Presentation:

Program No.	Presentation Title	Name	Affiliation
13-2 [BACUS]	Current Performance of Electron Multi-beam Mask Writers and Future Plans toward High-NA EUV Era	Jumpei Yasuda, Hiroshi Matsumoto, Haruyuki Nomura, Hayato Kimura, Keisuke Yamaguchi, Yoshinori Kojima, Masato Saito, Takao Tamura, Noriaki Nakayamada	NuFlare Technology, Inc., Japan
5-2	Reducing systematic LCDU of dense contact hole arrays on wafer via source optimization	Joern-Holger Franke ¹ , Alberto Colina ² , Lieve Van Look ¹ , Andreas Frommhold ¹ , Gijsbert Rispen ² , Eelco van Setten ² , Mark Maslow ²	imec, Belgium ¹ ASML Netherlands B.V., The Netherlands ²
6-2	Exploring Photomask Etching Capabilities For New EUV Absorber Materials	Rebecca Stern, Jeff Chen, Rao Yalamanchili	Applied Materials, USA

Best Poster Presentation:

Program No.	Presentation Title	Name	Affiliation
8-8 [EMLC]	A Study of Photomask Manufacture Process based on AI Technology	Hiroshi Nakata, Ikuo Kikuchi, Noriko Baba, Maiko Hikichi, Shingo Yoshikawa	Dai Nippon Printing Co., Ltd., Japan

Best Academic Poster Presentation:

Program No.	Presentation Title	Name	Affiliation
8-2	Evaluation of suprathreshold ions in a laser-produced plasma beyond-EUV source	Takeru Niinuma ¹ , Tsukasa Sugiura ¹ , Masaki Kume ¹ , Yuto Nakayama ¹ , Hiroki Morita ¹ , Atsushi Sunahara ² , Shinichi Namba ³ , Takeshi Higashiguchi ¹	Utsunomiya University, Japan ¹ Purdue University, USA ² Hiroshima University, Japan ³